Form PTO-1449 (modified) SERIAL NO. 09/779,123 List of Patents and Publications APPLICANT: Sethuraman et al. GROUP: Unknown For Applicant's Information Disclosure Statement (Use several sheets if necessary) 2827 FILING DATE: February 7, 2001 **U.S. PATENT DOCUMENTS** EXAM REI. APR 2 7 2001 FILING DATE IF DOCUMENT NUMBER CLASS **SUB** DATE NAME APPROPRIATE BRADEMARK OF **CLASS** INITIAL 4,010,583 3/1977 Highberg 284 Ottman et al. **B2** 4,393,628 7/1983 281 **B**3 5,294,570 Fleming, Jr. et al. 3/1994 M **B4** 5,602,423 2/1997 Jain 257 75 L **B**5 9/1997 Schonauer et al. 5,662,769 **B**6 Brunner et al. 5,695,572 12/1997 **B7** 5,782,675 7/1998 Southwick 56 **B8** 5,786,260 7/1998 Jang et al. 438 Walker et al. **B9** 5,919,082 7/1999 **B10** 5,963,841 10/1999 Karlsson et al. **B**11 5,972,124 10/1999 Sethuraman B12 Hudson 5,972,792 10/1999 **B13** Glass 6,010,964 1/2000 **B14** Moslehi 6,016,000 1/2000 B15 3/2000 Lin et al. 6,042,996 Gill, Ir. et al. **B16** 4,193,226 3/1980 **B17** 4,811,522 Gill, Jr. 3/1989 Schultz et al. **B18** 5,421,769 6/1995 FOREIGN PATENT DOCUMENTS TRANSLATION EXAM. REF. DOCUMENT NUMBER DATE **COUNTRY** CLASS **SUB** YES/NO **INITIALS** DES. **CLASS** OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) B19 Malkoe et al., "Effect of Retaining Ring System on the Polishing of 300 mm Oxide-Wafers," March 2001, pp. 519-522.

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